

Invite you to the

Laser Lithography and Direct Writing Technical Workshop & Discussion at the MNE, Rhodes, Greece

Date: Monday 23rd September, 2019
Time: 14:00 until 17:00
Venue: Rhodes Palace Hotel
Hall ALPHA, 1st floor of the
executive wing



We would be delighted to welcome you.
Participation is free. Please register your
planned attendance by sending an
e-mail to: workshopMNE@himt.de

Preliminary Agenda

14:00	Welcome & Introduction	
14:10	Daniel Braun, Heidelberg Instruments Mikrotechnik GmbH	The New Table-Top Maskless Aligner μ MLA
14:30	Lean Gottlieb Pedersen, DTU in Copenhagen	Maskless Lithography at the DTU
14:50	Anja Voigt, micro resist technology	Positive Tone Photoresists for Grayscale Laser Lithography
15:10	Vitaly Hanin, Weizmann Institute, Israel	OPC for Laser Writer
15:30	Coffee Break	
15:40	Nezih Unal, GenISys	BEAMER for Binary and Grayscale Laser Lithography
16:00	Irina Harder, Max Planck Institute Erlangen	High-Resolution Laser Lithography
16:20	Felix Holzner, SwissLitho AG	A New Integrated Mix & Match Direct-Write Nano- and Microlithography Platform
16:40	Summary & Discussion	
17:00	Closing	